

In the Claims

Applicant amends claims 1, 2, 13, 18 and 19 as described below. Please note that claim 13 has also been amended to comply with the 35 USC 112 rejection provided by the Examiner.

Additionally, the Applicant cancels claims 20 and 21 and reserves the right to prosecute these or similar claims in continuation applications, continuation-in-part patent application, and other such patent applications.

On the following page there is a MARKED-UP version of the replacement paragraph for the amendment to the Claim 1 located on Page 21, line 4 through line 14 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(iii).

1. A plasma processing chamber configured to generate a confined plasma to receive a gas, comprising:

 a first powered electrode configured to receive a workpiece, said first powered electrode having a first electrode area ;

 a power generator operatively coupled to said first powered electrode and configured to communicate power to said first powered electrode;

 a second electrode disposed at a distance from said first powered electrode, said first powered electrode and said second electrode configured to convert said gas to a plasma, said second electrode having have a second electrode area; and

a plurality of confinement rings surrounding said confined plasma; and

 a ground extension adjacent said first powered electrode and surrounding said first powered electrode.

On the following page there is a CLEAN version of the replacement paragraph for the amendment to Claim 1 located on Page 21, line 4 through line 14 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(ii).

1. A plasma processing chamber configured to generate a confined plasma, comprising:

a first powered electrode configured to receive a workpiece, said first powered electrode having a first electrode area ;

a power generator operatively coupled to said first powered electrode and configured to communicate power to said first powered electrode;

a second electrode disposed at a distance from said first powered electrode, said first powered electrode and said second electrode configured to convert said gas to a plasma, said second electrode having a second electrode area;

a plurality of confinement rings surrounding said confined plasma; and

a ground extension adjacent said first powered electrode and surrounding said first powered electrode.

On the following page there is a MARKED-UP version of the replacement paragraph for the amendment to the Claim 2 located on Page 21, line 16 through line 18 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(iii).

2. The plasma processing chamber of claim 1 wherein said plurality of confinement rings surround said first powered electrode and said second electrode, further comprising at least one confinement ring configured to confine said plasma, said at least one confinement ring surrounding said first powered electrode.

On the following page there is a CLEAN version of the replacement paragraph for the amendment to Claim 2 located on Page 21, line 16 through line 18 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(ii).

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2. The plasma processing chamber of claim 1 wherein said plurality of confinement rings surround said first powered electrode and said second electrode.

On the following page there is a MARKED-UP version of the replacement paragraph for the amendment to the Claim 13 located on Page 23, line 16 through Page 24, line 1 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(iii).

13. A plasma processing chamber configured to generate a confined plasma to receive a gas, comprising:

 a first powered electrode configured to receive a workpiece, said first powered electrode having a first electrode area ;

 a power generator operatively coupled to said first powered electrode and configured to communicate communicated power to said first powered electrode;

 a second electrode disposed at a distance from above said first powered electrode, said first powered electrode and said second electrode configured to convert said gas to a plasma, said second electrode having a second electrode area;

 a ground extension adjacent said first powered electrode and surrounding said first powered electrode, said ground extension separated from said first powered electrode by a dielectric; and

a plurality of confinement rings at least one confinement ring configured to confine said plasma, said at least one confinement ring surrounding said first powered electrode and said second electrode.

On the following page there is a CLEAN version of the replacement paragraph for the amendment to Claim 13 located on Page 23, line 16 through Page 24, line 1 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(ii).

13. A plasma processing chamber configured to generate a confined plasma, comprising:

a first powered electrode configured to receive a workpiece, said first powered electrode having a first electrode area ;

a power generator operatively coupled to said first powered electrode and configured to communicate power to said first powered electrode;

a second electrode disposed at a distance from said first powered electrode, said first powered electrode and said second electrode configured to convert said gas to a plasma, said second electrode having a second electrode area;

a ground extension adjacent said first powered electrode and surrounding said first powered electrode, said ground extension separated from said first powered electrode by a dielectric; and

a plurality of confinement rings surrounding said first powered electrode and said second electrode.

On the following page there is a MARKED-UP version of the replacement paragraph for the amendment to the Claim 18 located on Page 24, line 18 through Page 25, line 7 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(iii).

18. A method for generating a confined plasma in a plasma processing chamber including a plurality of confinement rings surrounding said confined plasma, said method comprising:

receiving a gas in said plasma processing chamber;

causing a first electrode to receive a workpiece, said first electrode operatively coupled to a power supply;

causing a second electrode disposed at a distance from said first electrode to receive RF power from said first electrode, said second electrode having a second electrode area that is greater than said first electrode area;

engaging a power supply to communicate RF power to said first electrode to generate a plasma; and

causing a ground extension adjacent said first electrode to drain a plurality of charge from said plasma.

On the following page there is a CLEAN version of the replacement paragraph for the amendment to Claim 18 located on Page 24, line 18 through Page 25, line 7 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(ii).

18. A method for generating a confined plasma in a plasma processing chamber

including a plurality of confinement rings surrounding said confined plasma, said method comprising:

receiving a gas in said plasma processing chamber;

causing a first electrode to receive a workpiece, said first electrode operatively coupled to a power supply;

causing a second electrode disposed at a distance from said first electrode to receive RF power from said first electrode, said second electrode having a second electrode area that is greater than said first electrode area;

engaging a power supply to communicate RF power to said first electrode to generate a plasma; and

causing a ground extension adjacent said first electrode to drain a plurality of charge from said plasma.

On the following page there is a MARKED-UP version of the replacement paragraph for the amendment to Claim 19 located on Page 25, line 9 through line 10 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(iii).

19. The method of claim 18 further comprising generating said confined plasma
due in part to said plurality of confinement rings and said ground extension, draining
said plurality of charge at a plasma boundary defined by at least one confinement
ring.

On the following page there is a CLEAN version of the replacement paragraph for the amendment to Claim 19 located on Page 25, line 9 through line 10 for Patent Application 10/077,072. This amendment complies with 37 CFR 1.121(b)(1)(ii).

19. The method of claim 18 further comprising generating said confined plasma
due in part to said plurality of confinement rings and said ground extension.

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